

Accepted Manuscript

Atmospheric pressure plasma jet processed reduced graphene oxides for supercapacitor application

Fei-Hong Kuok, Chen-Yu Liao, Ting-Hao Wan, Po-Wei Yeh, I-Chun Cheng, Jian-Zhang Chen



PII: S0925-8388(16)32790-6

DOI: [10.1016/j.jallcom.2016.09.056](https://doi.org/10.1016/j.jallcom.2016.09.056)

Reference: JALCOM 38890

To appear in: *Journal of Alloys and Compounds*

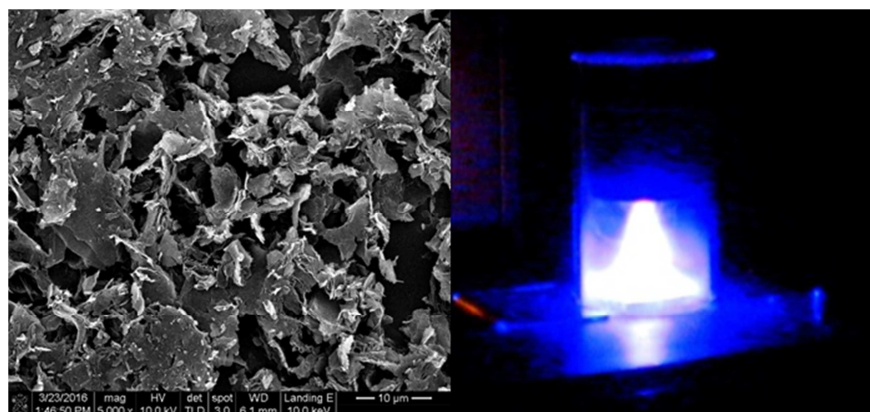
Received Date: 16 June 2016

Revised Date: 23 August 2016

Accepted Date: 5 September 2016

Please cite this article as: F.-H. Kuok, C.-Y. Liao, T.-H. Wan, P.-W. Yeh, I.-C. Cheng, J.-Z. Chen, Atmospheric pressure plasma jet processed reduced graphene oxides for supercapacitor application, *Journal of Alloys and Compounds* (2016), doi: 10.1016/j.jallcom.2016.09.056.

This is a PDF file of an unedited manuscript that has been accepted for publication. As a service to our customers we are providing this early version of the manuscript. The manuscript will undergo copyediting, typesetting, and review of the resulting proof before it is published in its final form. Please note that during the production process errors may be discovered which could affect the content, and all legal disclaimers that apply to the journal pertain.



ACCEPTED MANUSCRIPT

Download English Version:

<https://daneshyari.com/en/article/5461540>

Download Persian Version:

<https://daneshyari.com/article/5461540>

[Daneshyari.com](https://daneshyari.com)